

Positive Photoresist Developer

Product Code: PDN

PRODUCT DESCRIPTION

PDN is an aqueous alkaline developer for positive photoresists, in particular Electrolube PRP positive photoresist.

FEATURES

- * Safer in preparation and use than caustic soda.
- * Convenient solution form.
- * Long active life.
- * Buffered for repeatable, accurate images.
- * Good definition of resist image.
- * Economical in use.

DIRECTIONS FOR USE

Preparation

PDN should be diluted 1 part PDN to 4 parts demineralised water by volume and brought to 20-25°C for optimum performance (**not** below 20°C).

Application

After application and exposure of the photoresist the board should be immersed in the developer with gentle, continuous agitation (rocking) of the solution until a dark blue/purple image appears on a bright copper background. This should take 30-60 seconds. Do not mix this developer with any other developing chemical.

The development process is halted by rinsing the board thoroughly under running water. If the image appears in less than 20-25 seconds or appears very quickly then washes off completely the concentration of developer is too strong and additional demineralised water should be added until development occurs in 30-60 seconds. When development takes over 120 seconds the developer is exhausted and should be discarded and a fresh solution made up.

TECHNICAL
DATA
SHEET



**Copyright
Electrolube
2003**

All information is given in good faith but without warranty. Properties are given as a guide only and should not be taken as a specification. Electrolube cannot be held responsible for the performance of its products within any application determined by the customer, who must satisfy themselves as to the suitability of the product.



Positive Photoresist Developer – Page 2

After rinsing the image should be clear and well defined and the copper clear of any photoresist residue or particles. The board can then be etched using any conventional etching process compatible with the photoresist.

Removal of Undeveloped Photoresist

After etching the remaining photoresist it is best to remove the resist by rubbing with grade 000 wire wool (after the board has been drilled). Loose dust should be brushed away with a soft brush. Chemical removal with acetone (flammable) is also possible.

PACKAGING

250ml Bottle

ORDER CODE

PDN250ml

TECHNICAL DATA SHEET



Copyright Electrolube 2003

All information is given in good faith but without warranty. Properties are given as a guide only and should not be taken as a specification. Electrolube cannot be held responsible for the performance of its products within any application determined by the customer, who must satisfy themselves as to the suitability of the product.

